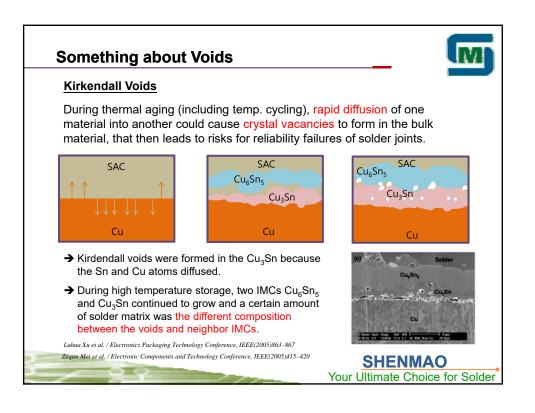
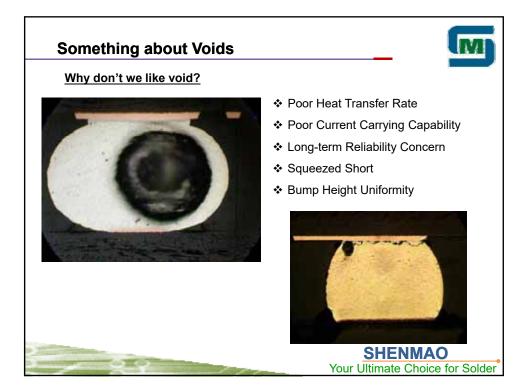


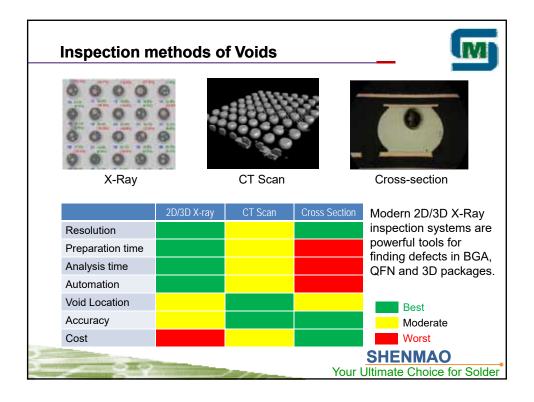




Types of Voids	Description
Macrovoids	Voids were formed as volatile ingredients of the fluxes within the solder paste, usually found everywhere in solder joint.
Planar Microvoids	Voids generated by anomalies in surface finish application process, generally located in one plane and found at the solder-to- land interface.
Shrinkage Voids	Caused by the solidification of SAC solders, formed as linear cracks with rough edges from the surface of the solder joints.
Micro-via Voids	Caused by microvias in lands.
Pinhole Voids	Voids generated by excursions in the copper plating process at board supplier.
0.0	1: Macrowskis

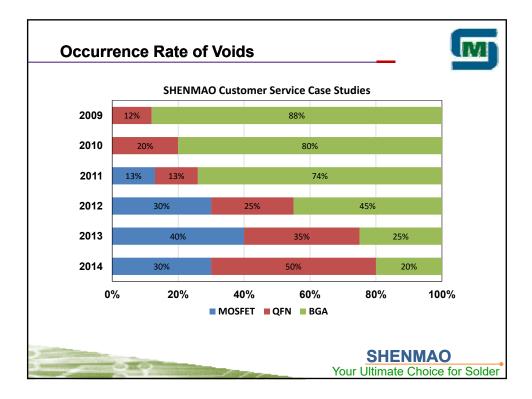


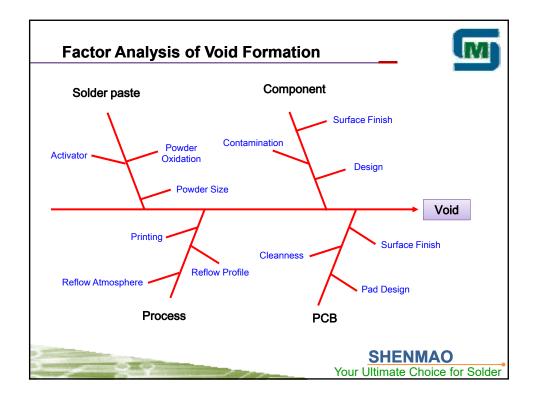


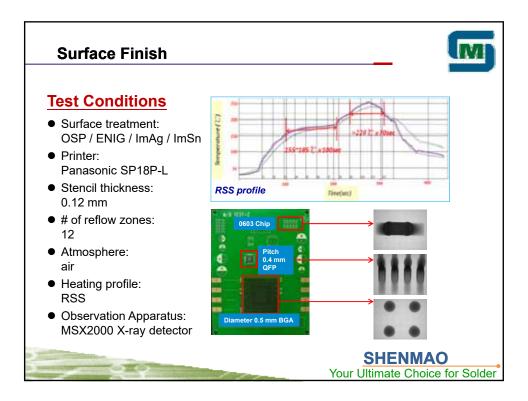


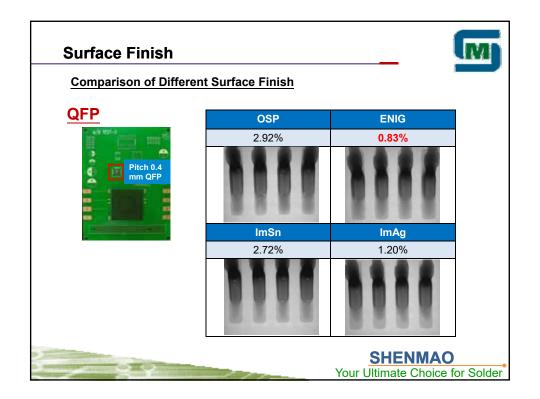


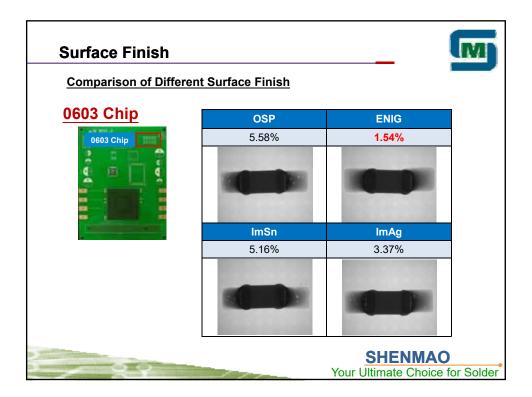
Component	Criteria	Standard
Solder Balls of BGA components (Pre-SMT)	< 15%	JESD 217
Surface Mount <u>Area Array</u> (Post-SMT)	< 25%	IPC-A-610
QFN, MOSFET, Components with Bottom Thermal Plane Terminations (Post-SMT)	No industrial standard but often target at < 25%	-

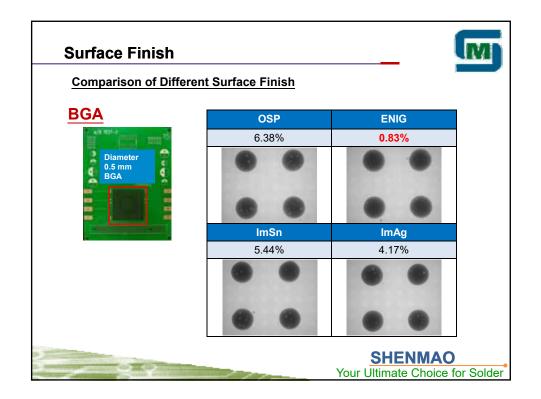


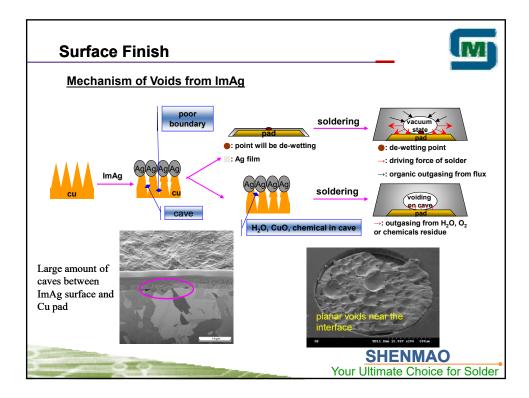


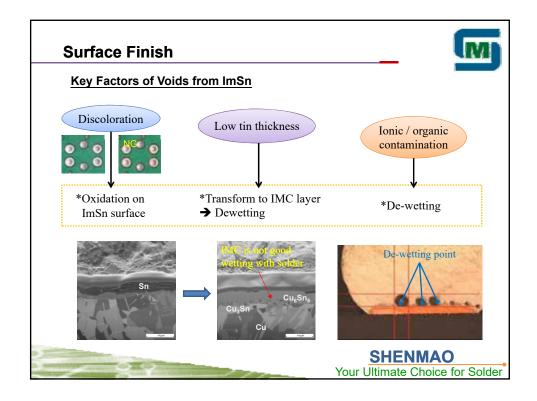


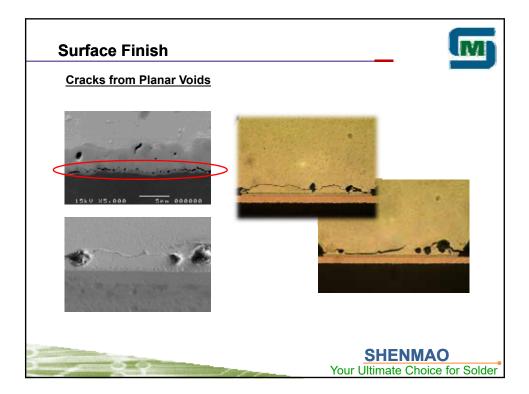


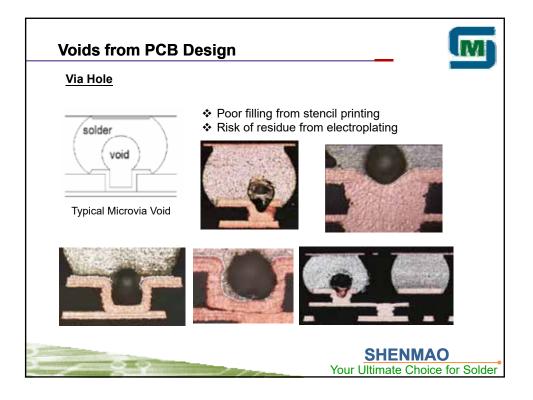


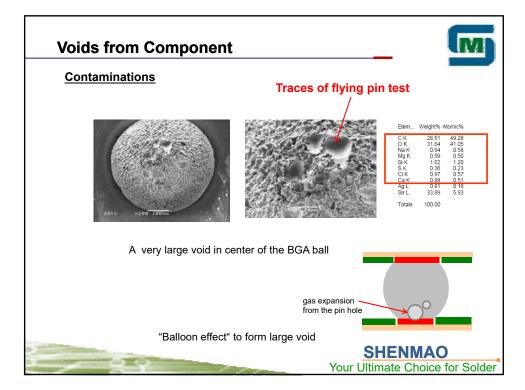


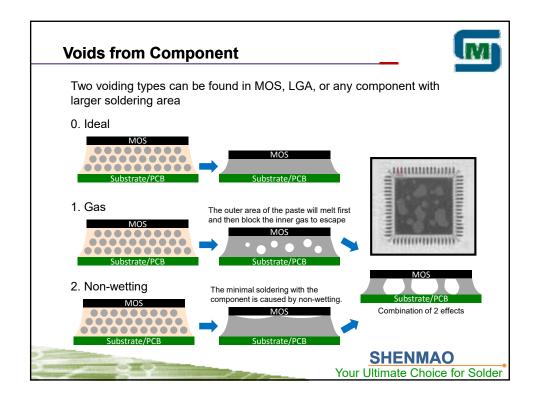


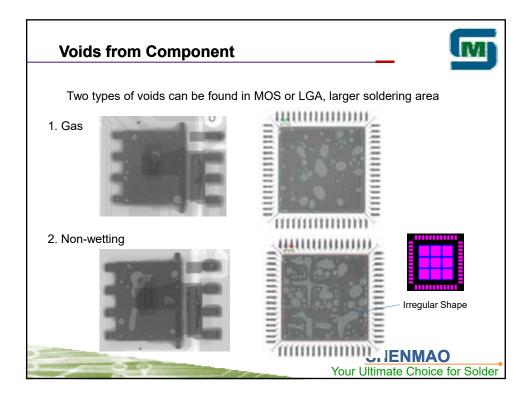


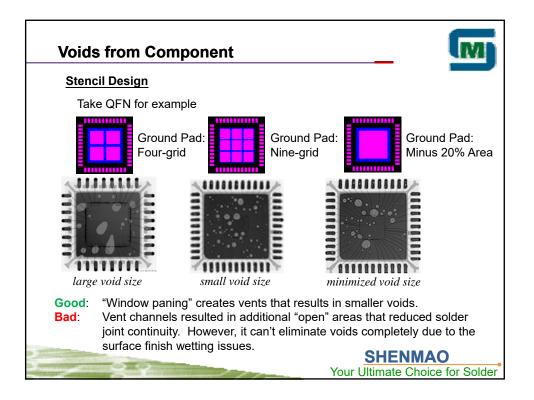


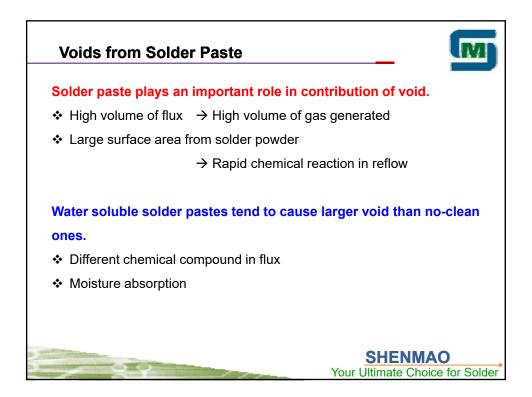


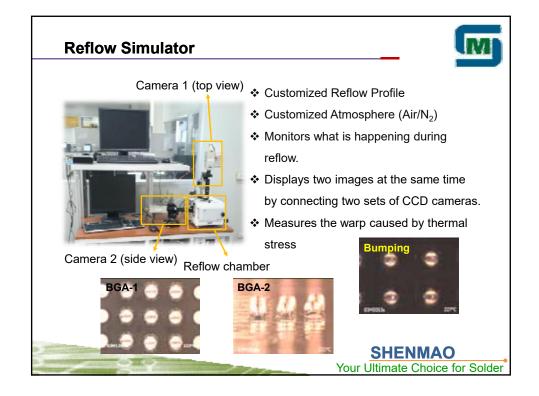


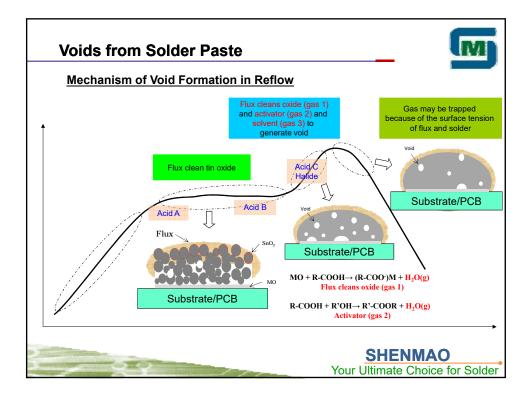


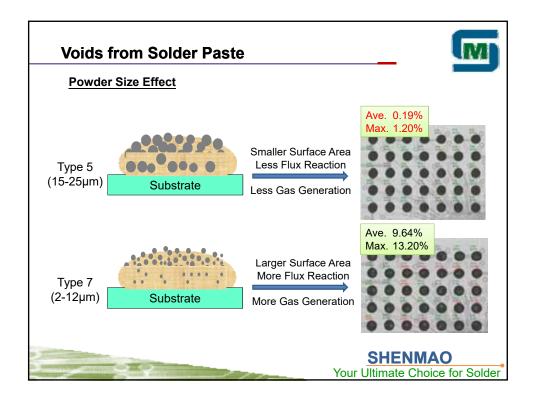


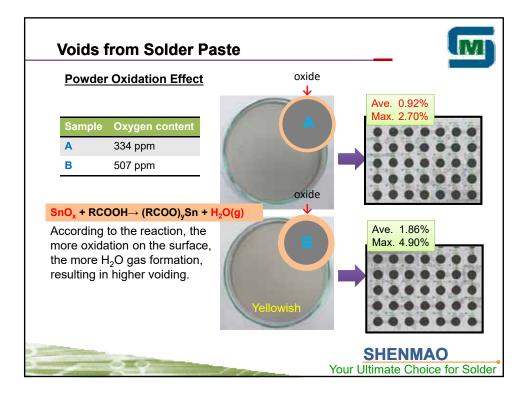


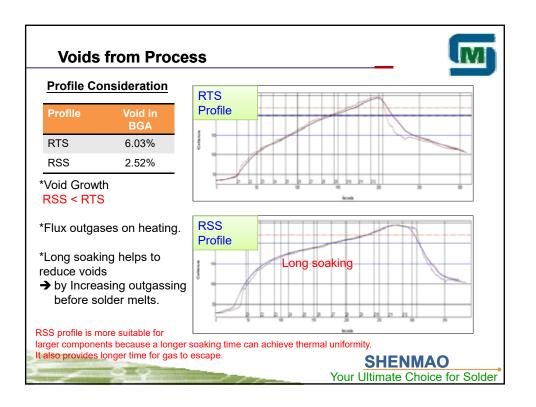




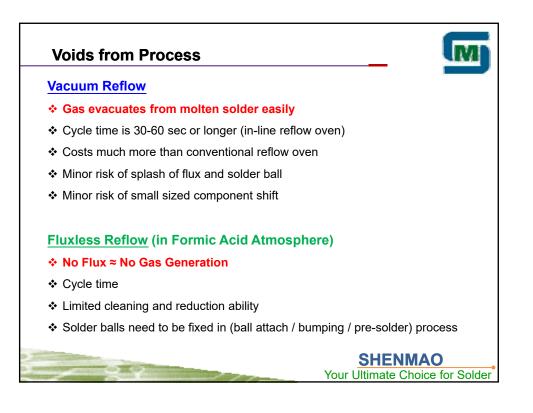


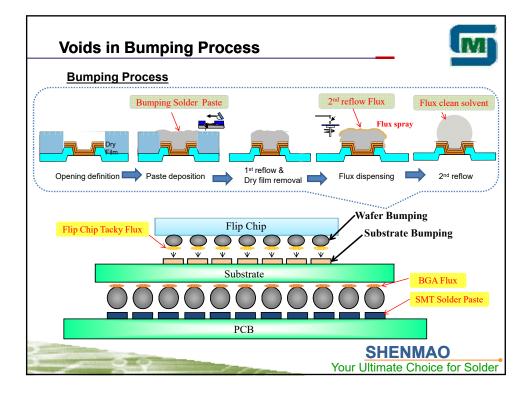


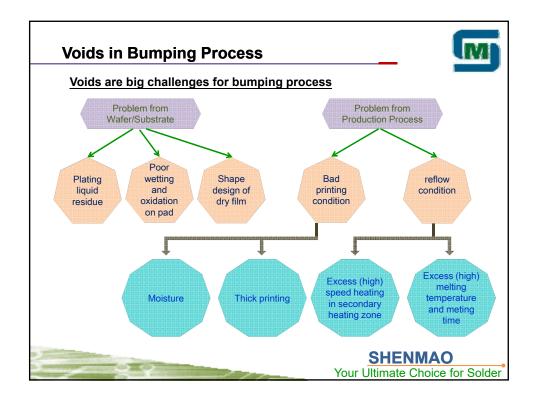




Voids from Proce	SS	M
<u>Atmosphere</u>		
 *Void Growth N₂ < Air N₂ prevents powder from oxidation. → Reduces gas formation from flux reaction during reflow In N₂ atmosphere, flux becomes more fluid (lower surface tension) so that the gas can escape easily. 	Ave. 2.28% Max. 5.70%	Ave. 1.27% Max. 3.60% Ave. 2.26% Max. 7.10%
		SHENMAO Your Ultimate Choice for Solder







Solder P	aste Des	<u>sign</u>		
Fh	1X	Conventional	New Formula	
Rosin	20~50%	R1	R1	
Activator	0~10%	A1+A2	A1+A2+A3	activity in flux
Halide	0~5%	H1	H2	
Thixotropic	0~10%	T1	T2	thixotropic property
Solvent	10~25%	S1+S2	S2+ <mark>S3</mark>	→ viscosity
n-house te	esting res	ults (piece wafe	er)	_
Conventio	nal	n state	side fields	Ave. 3.04% Max. 7.40%
New Form	ula	and and a	week	Ave. 1.03% Max. 3.90%

der Paste E n-Line Testir	Design ng Results (Full Waf	er)	
Wafer Type		Dummy	Dummy
Paste		Conventional	New Formula
Dry Film Opening (µm)		150	150
FV bump void (%)	Sample Size	7500	7500
	> 30	1	0
	26-30	8	4
	21-25	31	10
	16-20	56	16
	11-15	113	9
	Amount Void	209	39
	Void Rate (%)	2.78	0.52
	Max Void Size	31%	30%

